
Atomic Layer Deposition Applications 7

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Table of Contents

Preface	iii
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Chapter 1 Microelectronics

(Invited) Current and Future Applications of ALD in Micro-Electronics <i>I. J. Raaijmakers</i>	3
(Invited) Low Temperature Atomic Layer Deposition of Ru Thin Films with Enhanced Nucleation Using Various Ru(0) Metallorganic Precursors and Molecular O ₂ <i>S. Kim</i>	19
ALD Barrier Deposition on Porous Low-k Dielectric Materials for Interconnects <i>S. Van Elshocht, A. Delabie, S. Dewilde, J. Meersschaert, J. Swerts, H. Tielens, P. Verdonck, T. Witters, and E. Vancoillie</i>	25
Copper-ALD Seed Layer as an Enabler for Device Scaling <i>J. Mao, E. Eisenbraun, V. Omarjee, A. Korolev, and C. Dussarrat</i>	33
(Invited) Plasma Enhanced Atomic Layer Deposited Ruthenium for MIMCAP Applications <i>J. Swerts, M. Salimullah, M. Popovici, M. Kim, M. Pawlak, A. Delabie, M. Schaekers, K. Tomida, B. Kaczer, K. Opsomer, C. Vrancken, I. Debusschere, L. Altimime, J. Kittl, and S. Van Elshocht</i>	41
(Invited) ALD and AVD Grown Perovskite-type Dielectrics for Metal-Insulator-Metal Applications <i>C. Wenger, M. Lukosius, T. Blomberg, A. Abrutis, P. Baumann, and G. Ruhl</i>	53
Plasma-Assisted Atomic Layer Deposition of SrTiO ₃ : Stoichiometry and Crystallinity Study by Spectroscopic Ellipsometry <i>V. Longo, N. Leick, F. Roozeboom, and W. Kessels</i>	63
Low Equivalent Oxide Thickness TiO ₂ Based Capacitors for DRAM Application <i>K. Fröhlich, B. Hudec, K. Hušeková, J. Aarik, A. Tarre, A. Kasikov, R. Rammula, and A. Vincze</i>	73

Optimizing ALD HfO ₂ for Advanced Gate Stacks with Interspersed UV and Thermal Treatments- DADA and MDMA Variations, Combinations, and Optimization <i>R. D. Clark, S. Consiglio, G. Nakamura, Y. Trickett, and G. J. Leusink</i>	79
---	----

Structural Characteristics of Electrically Scaled ALD HfO ₂ from Cyclical Deposition and Annealing Scheme <i>S. Consiglio, R. D. Clark, E. Bersch, J. LaRose, I. Wells, K. Tapily, G. J. Leusink, and A. Diebold</i>	89
--	----

Chapter 2 **Nanotechnology**

(Invited) Tailor-Made, Magnetic Nanotubes by Template-Directed Atomic Layer Deposition <i>R. Zierold and K. Nielsch</i>	111
--	-----

ALD Applied to Conformal Coating of Nanoporous γ -Alumina: Spinel Formation and Luminescence Induced by Europium Doping <i>E. Rauwel, O. Nilsen, A. Galeckas, J. Walmsley, E. Rytter, and H. Fjellvåg</i>	123
---	-----

Metalcone and Metalcone/Metal Oxide Alloys Grown Using Atomic and Molecular Layer Deposition <i>B. Lee, V. Anderson, and S. George</i>	131
---	-----

Nanocomposites of ALD Hafnia Nanotubes Surface Functionalized with Gold Nanoparticles <i>T. Abdel-Fattah, D. Gu, and H. Baumgart</i>	139
---	-----

Chapter 3 **Reaction Mechanisms and Modeling**

Indium Oxide ALD Using Cyclopentadienyl Indium and Mixtures of H ₂ O and O ₂ <i>J. W. Elam, J. A. Libera, and J. N. Hryn</i>	147
---	-----

In Situ Gas-Phase Diagnostics for Titanium Nitride Atomic Layer Deposition <i>J. E. Maslar, W. Kimes, and B. Sperling</i>	157
--	-----

Diffusion-Reaction Model of ALD in Nanostructured Substrates: Analytic Approximations to Dose Times as a Function of the Surface Reaction Probability <i>A. Yanguas-Gil and J. W. Elam</i>	169
---	-----

(Invited) Reaction Mechanisms in ALD of Ternary Oxides <i>S. D. Elliott and O. Nilsen</i>	175
--	-----

Chapter 4 Equipment and Precursors

Picosun SUNALE ALD Systems for High Quality Nanocoatings - Bridging the Gap between R&D and Industrial Production	187
---	-----

M. Toivola, T. Lehto, W. Li, T. Pilvi, and P. J. Soininen

(Invited) High Throughput Atomic Layer Deposition for Encapsulation of Large Area Electronics	195
---	-----

J. Kools

ALD for a Sustainable Future - Paving the Way to a Cleaner World from Sub-Nanometer Level	203
---	-----

M. Toivola and T. Pilvi

Development of Novel Silicon Precursors for Low-Temperature CVD/ALD Processes	211
---	-----

K. Iwanaga, K. Tada, H. Chiba, T. Yamamoto, A. Maniwa, T. Yotsuya, and N. Oshima

Atomic Layer Deposition of AlN with Tris(Dimethylamido)Aluminum and NH ₃	219
---	-----

G. Liu, E. Deguns, L. Lecordier, G. Sundaram, and J. Becker

Chapter 5 Emerging Applications

Deposition and Characterization of Atomic Layer Deposited ZnS Thin Films on p-type GaSb(100) Using Diethylzinc Precursor and Hydrogen Sulfide	229
---	-----

R. Xu, J. Huang, S. Ghosh, and C. Takoudis

(Invited) Atomic Layer Deposition of Superconductors	237
--	-----

T. Proslie, J. Klug, N. C. Becker, J. W. Elam, and M. Pellin

Study of Atomic Layer Deposition of ZnO on a Polar Oxide Substrate by In Situ Quartz Crystal Microbalance	247
---	-----

K. Pradhan and P. F. Lyman

Atomic Layer Deposition of Antimony Telluride Thin Films Using (Me ₃ Si) ₂ Te with SbCl ₃ as Precursors	255
--	-----

D. Gu, D. Nminibapiel, H. Baumgart, H. Robinson, and V. Kochergin

Enabling High Performance Instruments for Astronomy and Space Exploration with ALD	263
--	-----

F. Greer, M. Hoenk, B. Jacquot, T. Jones, M. Dickie, S. Monacos, S. Nikzad, E. Hamden, D. Schmonivich, P. Day, and H. Leduc

Chapter 6

Photovoltaics, Batteries, and Fuel Cells

(Invited) Molecular Layer Deposition of Flexible, Transparent and Conductive Hybrid Organic-Inorganic Thin Films <i>B. Yoon, B. Lee, and S. George</i>	271
Novel Hybrid Organic/Inorganic Photovoltaic Device Configuration Utilizing ALD Technology and Template Based Nanoelectrode Arrays <i>D. Gu, H. Baumgart, and G. Namkoong</i>	279
Atomic Layer Deposited Oxides for Passivation of Silicon Photoelectrodes for Solar Photoelectrochemical Cells <i>B. Kalanyan and G. Parsons</i>	285
(Invited) Aluminum Oxide and Other ALD Materials for Si Surface Passivation <i>G. Dingemans and W. Kessels</i>	293
(Invited) Atomic Layer Deposition for Novel Dye-Sensitized Solar Cells <i>N. Tétreault, L. Heiniger, M. Stefk, P. L. Labouchère, E. Arsenault, N. K. Nazeeruddin, G. A. Ozin, and M. Grätzel</i>	303
(Invited) Atomic Layer Deposited Yttria Stabilized Zirconia Barrier Layer for Proton Conducting Oxide <i>J. Park, S. Kang, T. M. Gür, and F. Prinz</i>	315
Remote Plasma Atomic Layer Deposition of Thin Films of Electrochemically Active LiCoO ₂ <i>M. E. Donders, H. C. Knoops, W. Kessels, and P. H. Notten</i>	321
(Invited) ALD of Thin Films for Lithium-Ion Batteries <i>T. Aaltonen, V. Miikkulainen, K. Gandrud, A. Pettersen, O. Nilsen, and H. Fjellvåg</i>	331
Author Index	341